

## WEST Search History





DATE: Monday, February 12, 2007

Hide?	<u>Set</u> <u>Name</u>	<u>Query</u>	<u>Hit</u> <u>Count</u>
		<i>DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L8	L7 and l5	22
<input type="checkbox"/>	L7	134/2,3,19,26,28;216/96,99,108;438/906.ccls.	9637
		<i>DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L6	L3 and ((clean\$3 or wash\$3 or etch\$3 or oxid\$5) same ozon\$5) and (hydrofluoric or (hydrogen fluoride) or HF)	2
		<i>DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L5	L4 and ((clean\$3 or wash\$3 or etch\$3 or oxid\$5) same ozon\$5) and (hydrofluoric or (hydrogen fluoride) or HF)	500
<input type="checkbox"/>	L4	(wafer or substrate or workpiece or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sib.2")	8650
		<i>DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L3	(wafer or substrate or workpiece or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sib.2")	4214
		<i>DB=USPT; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L2	6323140.pn.	1
		<i>DB=PGPB; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L1	20010053585	1

END OF SEARCH HISTORY

## Searches for User *mkornnakov* (Count = 5180)

Queries 5131 through 5180.

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S #	Updt	Database	Query
<u>S5180</u>	<u>U</u>	PGPB,USPT,USOC	(134/2,3,19,26,28;216/96,99,108;438/906.ccls. )2 and ((wafer or substrate or workpiece or ( (
			semiconductor) with (anneal\$3 or heat\$3) with 1
			(hydrogen or "H.sib.2") and ((clean\$3 or
			wash\$3 or etch\$3 or oxid\$5) same ozon\$5) and
			(hydrofluoric or (hydrogen fluoride) or HF) )
<u>S5179</u>	<u>U</u>	PGPB,USPT,USOC	134/2,3,19,26,28;216/96,99,108;438/906.ccls. 2
			(
			)
<u>S5178</u>	<u>U</u>	EPAB,JPAB,DWPI,TDBD	((wafer or substrate or workpiece or 2
			semiconductor) with (anneal\$3 or heat\$3) with (
			(hydrogen or "H.sib.2") ) and ((clean\$3 or 1
			wash\$3 or etch\$3 or oxid\$5) same ozon\$5) and
			(hydrofluoric or (hydrogen fluoride) or HF)
<u>S5177</u>	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or workpiece or 2
			semiconductor) with (anneal\$3 or heat\$3) with (
			(hydrogen or "H.sib.2") ) and ((clean\$3 or 1
			wash\$3 or etch\$3 or oxid\$5) same ozon\$5) and
			(hydrofluoric or (hydrogen fluoride) or HF)
<u>S5176</u>	<u>U</u>	PGPB,USPT,USOC	(wafer or substrate or workpiece or 2
			semiconductor) with (anneal\$3 or heat\$3) with (
			(hydrogen or "H.sib.2") 1
<u>S5175</u>	<u>U</u>	EPAB,JPAB,DWPI,TDBD	(wafer or substrate or workpiece or 2
			semiconductor) with (anneal\$3 or heat\$3) with (
			(hydrogen or "H.sib.2") 1
<u>S5174</u>	<u>U</u>	USPT	6323140.pn. 2
			(
			)
<u>S5173</u>	<u>U</u>	PGPB	20010053585 2
			(
			)
<u>S5172</u>	<u>U</u>	PGPB,USPT,USOC	((((wafer or substrate or semiconductor) with. 2
			(anneal\$3 or heat\$3) with (hydrogen or (
			"H.sub.2")) same (ozon\$4 or "O.sub.3")) and (
			(hydrofluoric or HF or (hydrogen fluoride))

<u>S5171</u>	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same (ozon\$4 or "O.sub.3") ) and (134/2,3,26;438/906.ccls. )	2 ( (
<u>S5170</u>	<u>U</u>	PGPB,USPT,USOC	(134/2,3,26;438/906.ccls. ) and (((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same (ozon\$4 or "O.sub.3") and (hydrofluoric or HF or (hydrogen fluoride)) )	2 ( (
<u>S5169</u>	<u>U</u>	PGPB,USPT,USOC	134/2,3,26;438/906.ccls.	2 ( (
<u>S5168</u>	<u>U</u>	PGPB,USPT,USOC	134/2,3,26;438/906.ccls.	2 ( (
<u>S5167</u>	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same (ozon\$4 or "O.sub.3") ) and (hydrofluoric or HF or (hydrogen fluoride))	2 ( (
<u>S5166</u>	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same (ozon\$4 or "O.sub.3")	2 ( (
<u>S5165</u>	<u>U</u>	EPAB,JPAB,DWPI,TDBD	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same (ozon\$4 or "O.sub.3") same (hydrofluoric or HF or (hydrogen fluoride))	2 ( (
<u>S5164</u>	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same (ozon\$4 or "O.sub.3") same (hydrofluoric or HF or (hydrogen fluoride))	2 ( (
<u>S5163</u>	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same ((clean\$3 or wash\$3 or rins\$3 or oxid\$7) with (ozon\$4 or "O.sub.3") with (hydrofluoric or HF or (hydrogen fluoride)))	2 ( (
<u>S5162</u>	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same ((clean\$3 or wash\$3 or rins\$3 or oxid\$7) with (ozon\$4 or "O.sub.3"))	2 ( (
<u>S5161</u>	<u>U</u>	EPAB,JPAB,DWPI,TDBD	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) with (hydrogen or "H.sub.2")) same ((clean\$3 or wash\$3 or rins\$3 or oxid\$7) with (ozon\$4 or "O.sub.3"))	2 ( (
<u>S5160</u>	<u>U</u>	EPAB,JPAB,DWPI,TDBD	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2")) same ((clean\$3 or wash\$3 or rins\$3 or oxid\$7)) with (ozon\$4 or "O.sub.3"))	2 ( (
<u>S5159</u>	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate or semiconductor) with (anneal\$3 or heat\$3) adj7 (hydrogen or	2 (

S5158	<u>U</u>	PGPB,USPT,USOC	"H.sub.2")) same ((clean\$3 or wash\$3 or rins\$3 ( or oxid\$7)) with (ozon\$4 or "O.sub.3"))	2
S5157	<u>U</u>	EPAB,JPAB,DWPI	((wafer or substrate or semiconductor) with ((anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2")) same ((clean\$3 or wash\$3 or rins\$3 ( or oxidiz\$5)) with (ozon\$4 or "O.sub.3"))	2
S5156	<u>U</u>	PGPB,USPT,USOC	(wafer or substrate or semiconductor) with ((anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2")) with (clean\$3 or wash\$3 or rins\$3) ( with (ozon\$4 or "O.sub.3"))	2
S5155	<u>U</u>	EPAB,JPAB,DWPI	(wafer or substrate or semiconductor) with ((anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2")) with (clean\$3 or wash\$3 or rins\$3) (	2
S5154	<u>U</u>	PGPB,USPT,USOC	(wafer or substrate or semiconductor) with ((anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2")) with (clean\$3 or wash\$3 or rins\$3) (	2
S5153	<u>U</u>	EPAB,JPAB,DWPI	(wafer or substrate or semiconductor) with ((anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2"))	2
S5152	<u>U</u>	PGPB,USPT,USOC	(wafer or substrate or semiconductor) with ((anneal\$3 or heat\$3) adj7 (hydrogen or "H.sub.2"))	2
S5151	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate) with (anneal\$3 or heat\$3) with (hydrogen or "h.sub.2") same oxidiz\$5 ) same (hydrofluoric or HF)	2
S5150	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate) with (anneal\$3 or heat\$3) with (hydrogen or "h.sub.2") same oxidiz\$5 ) same (hydrofluoric or HF)	2
S5149	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate) with (anneal\$3 or heat\$3) with (hydrogen or "h.sub.2") ) same oxidiz\$5	2
S5148	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate) with (anneal\$3 or heat\$3) with (hydrogen or "h.sub.2") ) .same (ozon\$4 with water)	2
S5147	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate) with (anneal\$3 or heat\$3) with (hydrogen or "h.sub.2") ) same (ozon\$4 adj5 water)	2
S5146	<u>U</u>	PGPB,USPT,USOC	((wafer or substrate) with (anneal\$3 or heat\$3) with (hydrogen or "h.sub.2") ) same (ozon\$4 adj3 water)	2
S5145	<u>U</u>	PGPB,USPT,USOC	(wafer or substrate) with (anneal\$3 or heat\$3) with (hydrogen or "h.sub.2")	2
S5144	<u>U</u>	PGPB,USPT,USOC	(wafer or substrate) same ((anneal\$3 or heat\$3)	2

		with (hydrogen or "h.sub.2")) same	(
		(hydrofluoric or HF) same (ozon\$4 adj3 water)	1
<u>S5143</u>	<u>U</u>	EPAB,JPAB,DWPI	(wafer or substrate) same ((anneal\$3 or heat\$3)
		with (hydrogen or "h.sub.2")) same	(
		(hydrofluoric or HF) same (ozon\$4 adj3 water)	1
<u>S5142</u>	<u>U</u>	PGPB,USPT,USOC,EPAB,JPAB,DWPI	((toshiba ceramics).as. or izumome-koji\$.in. or
		sakurai-naoaki\$.in. or hayamizu-naoya\$.in. or	(
		yamabe-jyunsei\$.in. or ino-takao\$.in. or	1
		nagahama-hiromi\$.in. or kurita-hisatsugu\$.in. )	
		and ((wafer or substrate) same ((anneal\$3 or	
		heat\$3) with (hydrogen or "h.sub.2")) same	
		(hydrofluoric or HF) same (ozon\$4 adj3 water))	
<u>S5141</u>	<u>U</u>	PGPB,USPT,USOC,EPAB,JPAB,DWPI	((toshiba ceramics).as. ) or (izumome-koji\$.in. )
		or (sakurai-naoaki\$.in. ) or (hayamizu-	(
		naoya\$.in. ) or (yamabe-jyunsei\$.in. ) or (ino-	1
		takao\$.in. ) or (nagahama-hiromi\$.in. ) or	
		(kurita-hisatsugu\$.in. )	
<u>S5140</u>	<u>U</u>	PGPB,USPT,USOC,EPAB,JPAB,DWPI	(toshiba ceramics).as.
			(
			1
<u>S5139</u>	<u>U</u>	PGPB,USPT,USOC,EPAB,JPAB,DWPI	izumome-koji\$.in.
			(
			1
<u>S5138</u>	<u>U</u>	PGPB,USPT,USOC,EPAB,JPAB,DWPI	(izumome-koji)\$.in.
			(
			1
<u>S5137</u>	<u>U</u>	PGPB,USPT,USOC,EPAB,JPAB,DWPI	(shibata-izumome)\$.in.
			(
			1
<u>S5136</u>	<u>U</u>	PGPB,USPT,USOC,EPAB,JPAB,DWPI	((shibata-shi)-izumome)\$.in.
			(
			1
<u>S5135</u>	<u>U</u>	PGPB,USPT,USOC,EPAB,JPAB,DWPI	sakurai-naoaki\$.in.
			(
			1
<u>S5134</u>	<u>U</u>	PGPB,USPT,USOC,EPAB,JPAB,DWPI	hayamizu-naoya\$.in.
			(
			1
<u>S5133</u>	<u>U</u>	PGPB,USPT,USOC,EPAB,JPAB,DWPI	yamabe-jyunsei\$.in.
			(
			1
<u>S5132</u>	<u>U</u>	PGPB,USPT,USOC,EPAB,JPAB,DWPI	ino-takao\$.in.
			(
			1
<u>S5131</u>	<u>U</u>	PGPB,USPT,USOC,EPAB,JPAB,DWPI	nagahama-hiromi\$.in.
			(
			1